Inside Cover

Ji-Hyun Jang, Dhananjay Dendukuri, T. Alan Hatton, Edwin L. Thomas,* and Patrick S. Doyle*

Stop-flow interference lithography inside a poly(dimethylsiloxane) microfluidic device is described by E. L. Thomas, P. S. Doyle, and co-workers in their Communication on page 9027 ff. This new route enables the fabrication of large numbers of three-dimensionally patterned, mask-defined, polymeric particles with sub-micrometer features. A wide range of monomers can be used to create complex overall particle shapes that have designed interior architectures and porosities.

